

**PATENT**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of:

**Wang Yueh, et al.**

Application No.: 10/750,042

Filed: December 30, 2003

For: A LOW OUTGASSING AND NON-CROSSLINKING SERIES OF POLYMERS FOR EUV NEGATIVE TONE PHOTORESISTS

Examiner: Amanda C. Walke

Art Unit: 1795

Confirmation No.: 9165

**Mail Stop Amendment**

Commissioner For Patents

P.O. Box 1450

Alexandria, VA 22313-1450

**RESPONSE TO OFFICE ACTION**

In response to the Office Action mailed January 7, 2008, Applicant respectfully requests reconsideration of the above-identified patent application in light of the following.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 8 of this paper.

**Conclusion** begins on page 10 of this paper.

**Filed via EFS Web: May 7, 2008**